

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

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| In Re Application of: |) | |
| |) | |
| Song et al. |) | Group Art Unit: 1752 |
| |) | |
| Serial No.:10/720,966 |) | Examiner: John S. Y. Chu |
| |) | |
| Filed: November 24, 2003 |) | Confirmation No.: 5221 |
| |) | |
| For: PHOTORESIST COMPOSITION |) | TKHR Docket: 250913-1030 |
| AND METHOD PATTERN |) | Top-Team: 0424-8857US |
| FORMING USING THE SAME |) | |

RESPONSE TO FINAL OFFICE ACTION

Mail Stop AF
Commissioner for Patents
P.O. Box 1450
Alexandria, Virginia 22313-1450

Sir:

The FINAL Office Action mailed November 14, 2006, has been carefully considered. In response thereto, Applicants hereby submit following remarks and the accompanying petition for a 2-month extension of time. Reconsideration and allowance of the application and presently pending claims, as amended, are respectfully requested.